

**CLAIM AMENDMENT**

Please **CANCEL** claims 1-26 without prejudice or disclaimer.

Please **ADD** new claims 27-46, as follows.

1-26. (Currently Cancelled)

27. (Currently Added) A method for manufacturing a liquid crystal display (LCD),  
comprising steps of:

forming a color filter layer on a substrate;

forming a conductive layer on the color filter layer; and

forming a protrusion and a spacer on the conductive layer,

wherein the protrusion and a spacer are formed of the same material and the spacer is  
taller than the protrusion.

28. (Currently Added) The method of claim 27, wherein the step of forming the  
protrusion and the spacer comprises steps of:

forming an organic insulating layer on the conductive layer; and

patterning the organic insulating layer to form the protrusion and the spacer.

30. (Currently Added) The method of claim 29, wherein the step of patterning the organic insulating layer comprises steps of:

preparing a mask layer having an opaque area, a semitransparent area and a transparent area on predetermined areas thereof;

exposing the photosensitive organic insulating film to a light beam through the mask layer; and

developing the photosensitive organic insulating layer to form the protrusion and the spacer.

31. (Currently Added) The method of claim 30, wherein the spacer is formed at a portion of the photosensitive organic insulating layer corresponding to the opaque layer and the protrusion is formed at a portion of the photosensitive organic insulating layer corresponding to the semitransparent pattern.

32. (Currently Added) The method of claim 30, wherein the spacer is formed at a portion of the photosensitive organic insulating layer corresponding to the transparent layer and the protrusion is formed at a photosensitive portion of the organic insulating layer corresponding to the semitransparent pattern.

patterning the insulating layer and photoresist layer to form the protrusion and the spacer.

34. (Currently Added) The method of claim 33, wherein the step of patterning the insulating layer and photoresist layer comprising steps of:

preparing a mask layer having an opaque area, a semitransparent area and a transparent area on predetermined areas thereof;

exposing the photoresist layer to a light beam though the mask layer;

developing the photoresist layer to expose portions of the insulating layer; and

etching the exposed portions of the insulating layer.

35. (Currently Added) The method of claim 34, wherein the insulating layer contains silicon.

36. (Currently Added) The method of claim 27, further comprising a step of forming a black matrix layer on the substrate.

37. (Currently Added) The method of claim 36, wherein the black matrix layer is formed between the substrate and the color filter layer.

39. (Currently Added) A method for manufacturing a liquid crystal display (LCD), comprising steps of:
- forming a black matrix layer on a first substrate, the black matrix layer comprising a first black matrix pattern surrounding a pixel region and a second black matrix pattern formed within the pixel region;
  - forming a color filter layer on the black matrix layer;
  - forming a conductive layer on the color filter layer; and
  - forming a protrusion on a portion of the conductive layer corresponding to the second black matrix pattern, the protrusion having a height to maintain a predetermined gap between the first substrate and a second substrate facing the first substrate.
40. (Currently Added) The method of claim 39, wherein the height of the protrusion ranges between 3.0  $\mu\text{m}$  and 4.5  $\mu\text{m}$ .
41. (Currently Added) The method of claim 39, wherein the protrusion is pillar-shaped.
42. (Currently Added) The method of claim 41, wherein a top surface and a bottom surface of the protrusion have a circular or rectangular shape or a rectangular shape with curved

43. (Currently Added) The method of claim 39, wherein the protrusion is formed of a photosensitive material, positive or negative photoresist or an insulating material containing silicon.

44. (Currently Added) The method of claim 39, wherein the pixel region is divided into a plurality of sub-regions and the protrusion is formed within each sub-region.

45. (Currently Added) The method of claim 44, wherein the protrusion is formed at the center of each sub-region.

46. (Currently Added) The method of claim 39, wherein the protrusion is in contact with a pixel electrode of the second substrate to maintain the predetermined gap between the first substrate and the second substrate.